

## Method and apparatus for conditioning a polishing pad

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**Inventor:** FINKELMAN ALEX (US)

**Applicant:** LAM RES CORP (US)

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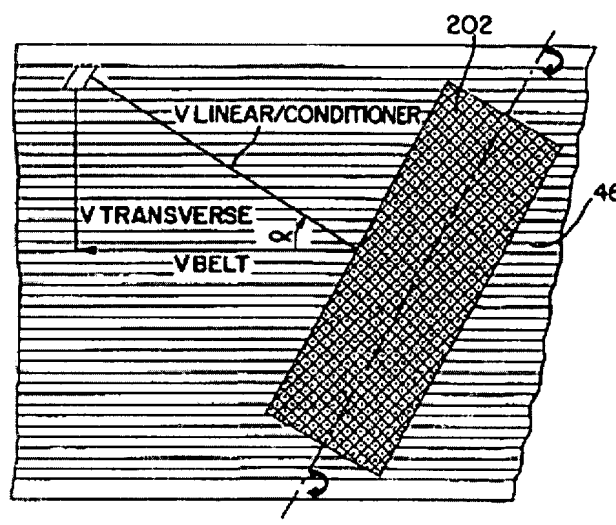
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### Abstract of TW471992B

A method and apparatus for conditioning a polishing pad is described. The method includes steps of moving a cylindrical roller having an abrasive substance affixed to it against a moving polishing pad. The roller may be actively rotated or reciprocated at variable rates, while maintaining a pressure against the polishing pad. The apparatus includes a cylindrical roller to one another or more pressure application devices mechanically connected to the roller.



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